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\*\* CONTINUING DATA \*\*\*\*\* *Ac*  
 This application is a CIP of 10/164,327 06/05/2002 PAT 6,939,434 *Ac*

\*\* FOREIGN APPLICATIONS \*\*\*\*\* *Ac*  
*none*

IF REQUIRED, FOREIGN FILING LICENSE GRANTED  
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35 USC 119 (a-d) conditions met <input type="checkbox"/> yes <input checked="" type="checkbox"/> no <input type="checkbox"/> May after allowance				
Verified and Acknowledged	Examiner's Signature <i>[Signature]</i>	Initials <i>[Initials]</i>		

ADDRESS

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TITLE

Plasma immersion ion implantation process using a capacitively coupled plasma source having low dissociation and low minimum plasma voltage

☐ All Fees